

Supporting Information Available:

## Metallic and Ionic Fe Induced Growth of Si-SiO<sub>x</sub> Core-shell Nanowires

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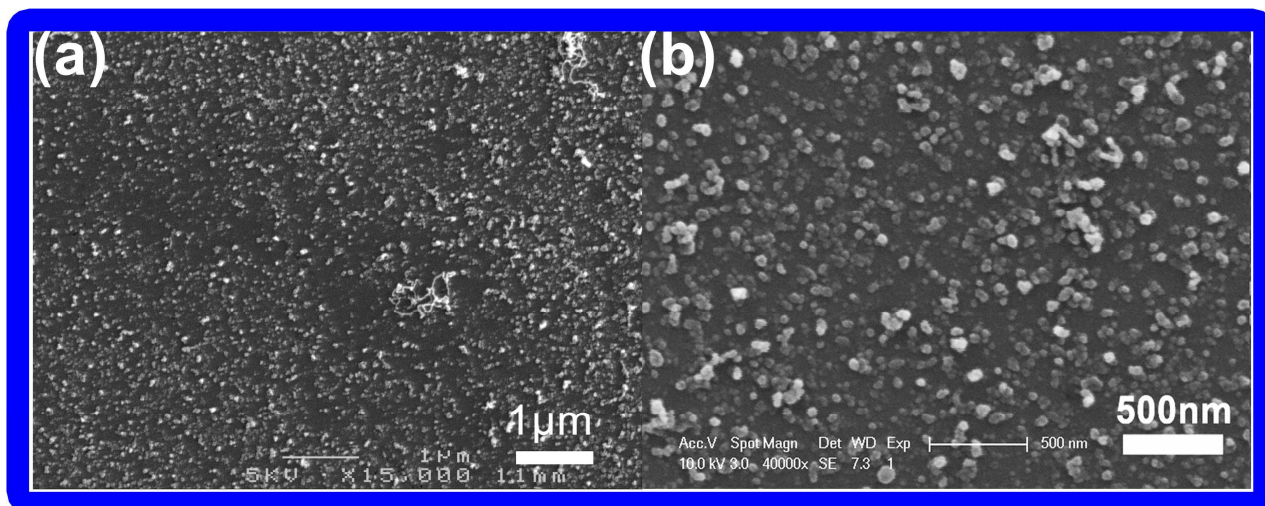


Figure S1a is a low magnification SEM image of the Si wafer covered with the Fe film annealing at 1000 °C, showing large quantities of nanosized particles formed on the wafer surface. Figure S1b is a close-up view of the SEM image and shows that the nanosized particles have a size distribution of 20-100 nm.